

AFTIFW  
PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE



Applicants: Young Sun Hwang et al. )

Serial No.: 10/719,083 )

Filed: November 21, 2003 )


For: Methods for Forming Fine  
Photoresist Patterns )

Group Art Unit: 1765 )

Examiner: Patricia Ann George )

Confirmation No. 2261 )

I hereby certify that this paper and the documents referred to as enclosed therewith are being deposited with the United States Postal Service as first class mail, postage prepaid, on August 2, 2006, in an envelope addressed to MS Amendments, Commissioner for Patents, P.O. Box 1450, Alexandria, Virginia 22313-1450

  
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AMENDMENT "B" AFTER FINAL REJECTION

MS Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, Virginia 22313-1450

Dear Sirs:

Please amend this application as follows:

the amendment to the claims section (along with a complete listing of claims) begins on page 2 of this paper;

the remarks section begins on page 5 of this paper.